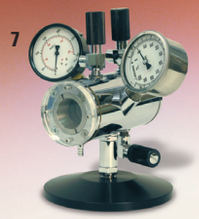
The SPI Supplies Family of Instruments



Excellence in sample preparation
just a click away... 2spi.com

Your results will never be better than your sample preparation. See how SPI Supplies can help you deliver the highest quality results for all your SEM/EDS, TEM and FESEM applications.

1. **Osmium Plasma Coaters** for FESEM Applications
2. **SPI-MODULE™** Sputter/Carbon Coater Module
3. **Plasma Prep™ III** Solid State Plasma Cleaner for cleaning TEM holders
4. **Plasma Prep™ X** Parallel Plate Plasma Etcher
5. **Plasma Prep™ III** Plasma Etcher with **PPIII Process Controller**
6. **Vacu Prep™ II** Turbo Pump Evaporation System
7. **SPI-DRY™** Critical Point Dryer
8. **Precision Spin Coater** Spin coater

SPI® SUPPLIES

SPI Supplies Division of **STRUCTURE PROBE, Inc.**

P.O. Box 656 • West Chester, PA 19381-0656 USA
Phone: 1-610-436-5400 • 1-800-2424-SPI (USA and Canada) • Fax: 1-610-436-5755 • 2spi.com • E-mail: sales@2spi.com

SPI Supplies Family of Instruments

SPI Module™ Sputter/Carbon Coaters

Combination sputter/carbon coater system for everyday routine SEM/EDS sample preparation. Fast and easy to use.

SPI-Dry™ Critical Point Dryers

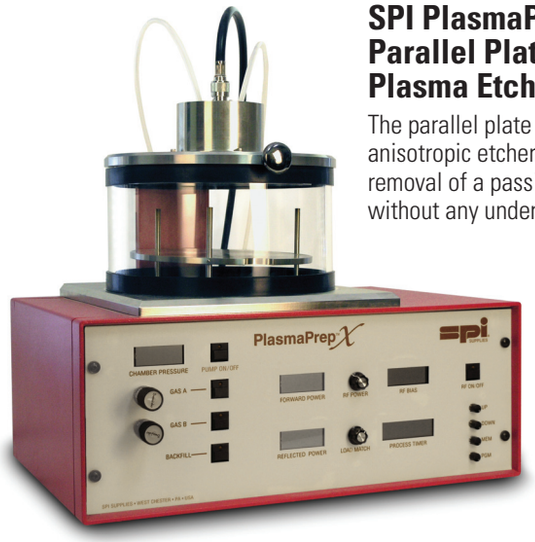
Used in applications in electron microscopy as well as aerogels and MEMS, the critical point drying is a method of drying samples without collapsing or deforming the structure of wet, fragile specimens.

Plasma Prep™ III

Solid state compact tabletop design with RF power range of 1 to 100W. The Plasma Prep™ III Process Controller: Add-on module with multiple gas inputs and process timer control.

SPI Plasma Prep™ III Plasma Cleaner

Compact bench-top sized plasma cleaner, that uses the "dry plasma process" for the removal of contamination on the TEM specimen stages

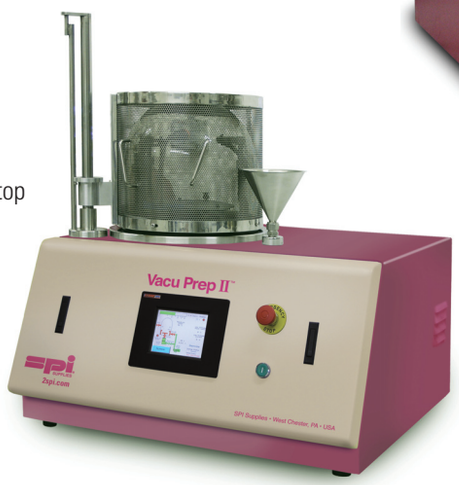


SPI PlasmaPrep™ X Parallel Plate Plasma Etcher

The parallel plate design of an anisotropic etcher permits the removal of a passivation layer without any undercutting.

SPI Supplies Vacu Prep™ II

Fast, clean, efficient, turbo-pumped, high vacuum bench-top evaporator with simple automated operation for evaporation or sputtering.



Osmium Plasma Coaters

The must have coater for high resolution FE-SEM work. Typical thickness of 1nm to 3nm of osmium metal, with excellentelectrical and thermal conductivity and a virtually "amorphous" coating with no discernible gain structure.